

1 PACKAGE SUBSTRATE FOR IMPROVING ELECTRICAL PERFORMANCE

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3 FIELD OF THE INVENTION

4 The present invention relates to a package substrate for semiconductor packages,
5 and more particularly to a package substrate with ground/power layers for improving
6 electrical performance.

7 BACKGROUND OF THE INVENTION

8 Conventionally, package substrates are used as chip carriers and electrical
9 interconnections for semiconductor packages. Wiring layouts in the substrates are to
10 serve as electrical connections with signal electrodes, ground and power electrodes of
11 chips. R.O.C. Patent No. 490818 entitled "substrate for semiconductor chip package"
12 discloses a package substrate having a chip-attaching region. A ground ring and a
13 power ring are formed on top surface of the substrate. A plurality of first contact pads
14 and second contact pads are formed on bottom surface of the substrate for bonding solder
15 balls. The first contact pads are located below the perimeter of ground ring and the
16 power ring, and are divided into two groups. The first group of the first contact pads is
17 electrically connected with the ground ring for connecting ground electrodes of the chip.
18 The second group of the first contact pads is electrically connected with the power ring
19 for connecting power electrodes of the chip. The second contact pads are arranged
20 around the first contact pads so as to electrically connect signal electrodes of the chip.

21 In order to improve the electrical performance of a semiconductor package, the
22 substrate includes at least one ground/power layer between the contact pads and the
23 ground/power ring. A substrate using a multi-layer PWB is disclosed in R.O.C. Patent
24 No. 434664 entitled "lead-bond type chip package and manufacturing method thereof".
25 The substrate includes an interlayer circuit board having prepreg disposed thereon. The
26 interlayer circuit board possesses a metal ground/power plane so as to connect the
27 ground/power source. Nevertheless, when a plurality of through holes are massively

1 formed on multi-layer substrate for electrically connecting with lead fingers (signal), the
2 through holes can not electrically be connected with the ground/power plane by forming
3 a plurality of openings in the ground/power plane. Therefore, each opening is round
4 corresponding to each through hole in position, enables the through holes to electrically
5 insulate against the ground/power plane. However, electrical performance of the
6 package substrate will be impaired when the through holes in the ground/power plane are
7 mass and in irregular distribution.

8 SUMMARY

9 The primary object of the present invention is to provide a package substrate for
10 improving electrical performance. A plurality of openings are formed in the
11 ground/power layer in a manner that the inner through holes electrically connected with
12 inner fingers are divided into a plurality of groups to pass through corresponding
13 openings in the format of grid array. The ground/power layer has a strip-shaped region
14 between adjacent openings to improve electrical performance of a metal ring and the
15 ground/power layers.

16 According to the present invention, the package substrate includes a first insulating
17 layer, a wiring layer and at least a ground/power layer. The first insulating layer has a
18 top surface and a bottom surface, and the top surface includes a chip-attaching region.
19 A wiring layer is formed on the top surface of the first insulating layer, which includes a
20 plurality of inner fingers and a plurality of outer fingers for electrically connecting with a
21 chip. A plurality of inner through holes and a plurality of outer through holes are
22 formed through the first insulating layer to electrically connect corresponding inner
23 fingers and outer fingers respectively. The ground/power layer is disposed on the
24 bottom surface of the first insulating layer and has a plurality of openings. Each
25 opening permits the inner through holes being divided into a plurality of groups to pass
26 through the ground/power layer with electrical isolation. Each group of inner through
27 holes passes through corresponding opening in grid array or radial arrangement. Thus

1 the ground/power layer between two adjacent openings has a strip-shaped region.
2 Preferably, a distance between two adjacent openings is not less than 0.2mm for
3 improving electrical performance.

4 DESCRIPTION OF THE DRAWINGS

5 Fig.1 is a cross-sectional view illustrating a package substrate for improving
6 electrical performance of an embodiment of the present invention.

7 Fig.2 is a top view illustrating the first insulating layer of package substrate for
8 improving electrical performance of the embodiment of the present invention.

9 Fig.3 is a cross-sectional view illustrating a ground/power layer formed on the
10 package substrate for improving electrical performance of the embodiment of the present
11 invention.

12 Fig.4 is a partial cross-sectional view illustrating the package substrate for
13 improving electrical performance used in a semiconductor package.

14 DEATAIED DESCRIPTION OF THE PRESENT INVENTION

15 Referring to the attached drawings, the present invention will be described by means
16 of the embodiments below.

17 As showed in Fig.1, according to the present invention a package substrate 100 for
18 improving electrical performance mainly comprises a first insulating layer 110, a wiring
19 layer and at least a ground/power layer (which includes a ground layer 140 and a power
20 layer 150). The first insulating layer 110 is made of glass fiber reinforced resin of FR-4,
21 FR-5, BT resin, or a soft insulating layer, such as polyimide. The first insulating layer
22 110 has a top surface 111 and a bottom surface 112. The top surface 111 includes a
23 chip-attaching region 113 for attaching a semiconductor chip 200 (referring to Fig.1 and
24 4). The wiring layer is formed on top surface 111 of the first insulating layer 110. As
25 showed in Fig.1 and Fig.2, the wiring layer includes a plurality of inner fingers 121, a
26 plurality of outer fingers 131 and a plurality of traces 122, 132. The inner fingers 121
27 and the outer fingers 131 are distinguished according to the distances from the

1 chip-attaching region 113. The inner fingers 121 are closer to the chip-attaching region
2 113 than the outer fingers 131. Both the inner fingers 121 and outer fingers 131 are
3 used to electrically connect the signals of a semiconductor chip 200. Also, a plurality of
4 inner through holes 123 are electrically connected with the inner fingers 121 by
5 corresponding traces 122. A plurality of outer through holes 133 are electrically
6 connected with the outer fingers 131 by corresponding traces 132. The inner through
7 holes 123 and the outer through holes 133 are formed through the first insulating layer
8 110 to electrically connect the top surface 111 and the bottom surface 112. In this
9 embodiment, the wiring layer further includes a ground metal ring 160 and a power metal
10 ring 170 around the chip-attaching region 113. The inner fingers 121 are disposed
11 between the metal ring 160,170 and the outer fingers 131.

12 In this embodiment, as showed in Fig.1 and Fig.3, the ground layer 140 is formed on
13 the bottom surface 112 of the first insulating layer 110 as a ground for the chip 200,
14 which may be a copper foil or other metal foil. The package substrate 100 can further
15 includes a second insulating layer 180 disposed on the bottom surface 112 of the first
16 insulating layer 110 to sandwich the ground layer 140 between the first insulating layer
17 110 and the second insulating layer 180. At least a ground through hole 161 is formed
18 through the first insulating layer 110 so as to connect the ground metal ring 160 and the
19 ground layer 140 at different planes. The ground layer 140 has a plurality of openings
20 141. The openings 141 are arranged radially to the chip-attaching region 113 in a shape
21 of strip or circle, wherein the openings 141 in a strip-shaped are formed for passing
22 through a mass of inner through holes 123 crowded in groups. Thus the inner through
23 holes 123 are divided into a plurality of groups. Each group of the inner through holes
24 123 arranges in single-line or multi-line grid array and is formed through each
25 corresponding opening 141, but electrical isolated from the ground layer 140. Therefore
26 the ground layer 140 has a strip-shaped region between two adjacent openings 141. The
27 strip-shaped region of the ground layer 140 between two adjacent openings 141 is not

1 less than 0.2mm in width to provide a satisfied current path 142.

2 Besides, a power layer 150 may be formed on bottom surface of the second
3 insulating layer 180, and at least a power through hole 171 is formed in the package
4 substrate 100. The power through hole 171 passes through the first insulating layer 110
5 and the second insulating layer 180, and electrically connect the power metal ring 170
6 and the power layer 150. The power layer 150 has a plurality of openings 151. Each
7 group of the inner through holes 123 are corresponding to each opening 151 so as to pass
8 through the opening 151 in groups with electrical isolation from the power layer 150.
9 Each group of the inner through holes 123 is located in each corresponding opening 151
10 in the format of grid array. The openings 151 of the power layer 150 are similar to the
11 openings 141 of the ground layer 140 mentioned above. The power layer 150 has a
12 strip-shaped region (not showed in the drawings) between two adjacent openings 151 so
13 as to improve electrical performance.

14 Referring to Fig.4, when the package substrate 100 mentioned-above is used for a
15 semiconductor package, a semiconductor chip 200, such as a microprocessor,
16 microcontroller or chip with high-density terminals, is attached to the chip-attaching
17 region 113 of the package substrate 100. The chip 200 has a plurality of bonding pads
18 210 on active surface thereof. The bonding pads 210 are divided into ground bonding
19 pads, power bonding pads and signal bonding pads. The ground bonding pads among
20 the bonding pads 210 of the chip 200 are electrically connected with the ground metal
21 ring 160 by bonding wires 221. The power bonding pads among the bonding pads 210
22 of the chip 200 are electrically connected with the power metal ring 170 by bonding
23 wires 222, some of the signal bonding pads among the bonding pads 210 of the chip 200
24 are electrically connected with the inner fingers 121 by bonding wires 223, and the rest of
25 signal bonding pads among the bonding pads 210 of the chip 200 are electrically
26 connected with the outer fingers 131 by bonding wires 224. The inner through holes
27 123 pass through the openings 141 of the ground layer 140 and the openings 151 of the

1 power layer 150 in groups, moreover, the openings 141,151 are densely designed to
2 ensure the ground layer 140 and the power layer 150 have the strip-shaped region for
3 improving electrical performance of the semiconductor package.

4 Besides, the present invention doesn't limit quantity of the insulating layer and the
5 wiring layer, a third insulating layer 190 or more insulating layer and more wiring layer
6 can be formed on bottom surface of the second insulating layer 180. A plurality of ball
7 pads for placing solder balls (not showed in the drawings) can be formed on the lowest
8 layer of insulating layer of the package substrate 100 and are electrically connected to
9 corresponding inner fingers 121, outer fingers 131, ground metal ring 160 and power
10 metal ring 170.

11 Moreover, the present invention doesn't limit relative location of the ground layer
12 140 and the power layer 150, the power layer 150 can be formed on the bottom surface
13 112 of the first insulating layer 110 or bottom surface of other insulating layers. Besides,
14 the inner through holes 123 also can easily formed in the package substrate 100 without
15 influencing the width of the ground/power layer 140 or 150 between the adjacent
16 openings 141 or 151. Each opening 141 or 151 allows at least one through hole 123 to
17 pass through, but openings 141 or 151 can be regularly arranged to close to each other
18 when there are many openings, such as in grid array or in radial arrangement, so that the
19 ground/power layer 140 or 150 still has a current path 142 which is more than 0.2mm in
20 width.

21 The above description of embodiments of this invention is intended to illustrate but
22 is not limited. Other embodiments of this invention will be obvious to those skilled in
23 the art in view of the above disclosure.

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